ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18 Stylesheet Version v18.0

> Title of Invention

Method for forming silicon dioxide film using siloxane

Application Number :

10/782094 4756

Confirmation Number: First Named Applicant:

Jae-Eun Park

Attorney Docket Number:

SAM-0483

Art Unit: Examiner:

Search string:

(20040096582).pn

US Published Applications

Note: Applicant is not required to submit a paper copy of cited US Published Applications

ini	Cite.No	Pub. No.	Date	Applicant	Kind	Class	Subclass
	1	20040096582	2004-05-20	Wang, et al.			

Remarks

Note: Remarks are not for responding to an office action.

Part 1 of 1.

Signature

Examiner Name	Date